

AMENDMENTS TO THE SPECIFICATION:

Please replace the paragraph beginning at page 1, line 12, with the following rewritten paragraph:

A' ~~--~~ The opposite substrate has a color filter (CF) and a black matrix. The color ~~filter~~ filter consists of color layers of red, green or blue arranged regularly. The black matrix is formed of a film with a light shielding property (opaque). The black matrix shields disclination of the liquid crystal to prevent a reduction in contrast. ~~--~~

Please replace the paragraph beginning at page 1, line 22, with the following rewritten paragraph:

Az ~~--~~ Here, the disclination refers to an alignment defect in which discontinuity occurs in the alignment direction of liquid crystal molecules due to a level difference in the alignment surface of liquid crystal, distribution of an electric field and an abrupt change in a driving voltage. Such liquid crystal alignment defect appears as a line or dot defect, resulting in deterioration of display quality. The disclination occurs in a display area overlapping with irregular portions on the surfaces of substrates, ~~ununiform~~ non-uniform portions of the liquid crystal alignment caused by variations in the degree of rubbing, and the like. ~~--~~

Please replace the paragraph beginning at page 4, line 17, with the following rewritten paragraph:

A3 ~~--The liquid crystal display device according to the~~
one aspect of the present invention, wherein said ~~insulating~~
insulating films may include a passivation film formed on the
switching element, a color layer formed on said passivation film,
and a flattening film formed on said passivation film and color
layer, ~~--~~

Please replace the paragraph beginning at page 5, line
20, with the following rewritten paragraph:

A4 ~~--Forming an insulating layer overlying the thin film~~
transistor and the wiring (14); ~~--~~

Please replace the paragraph beginning at page 6, line
18, with the following rewritten paragraph:

A5 ~~--FIG. 1 is a plane plan view of a liquid crystal display~~
device according to the present invention; ~~--~~

Please replace the paragraph beginning at page 6, line
26, with the following rewritten paragraph:

A6 ~~--FIG. 5 is a plane plan view illustrating the structure~~
of a liquid crystal display device according to a comparison;
and ~~--~~

Please replace the paragraph beginning at page 7, line 8,
with the following rewritten paragraph:

A7 ~~--FIG. 1 is a plane plan layout of a unit pixel area 11a~~
on a TFT substrate 100 of an active matrix liquid crystal display
device 11 according to this embodiment. FIG. 2 shows a cross-

A7
sectional structure of the active matrix liquid crystal display device 11. This cross-sectional view corresponds to a cross section taken in the direction of the arrows along line A-A' of TFT substrate 100 shown in FIG. 1, a cross section taken in the direction of the arrows along line B-B' thereof, and a cross section of end portion thereof. --

Please replace the paragraph beginning at page 8, line 5, with the following rewritten paragraph:

A8
-- The second projecting portion 12b has a shield portion 12ba and a capacitance portion 12bb. The shield portion 12ba has a substantially square shape, overlaps the region for a contact hole ~~108~~ 18 and shields it, as described later. It should be noted that an opening 12c for suppressing parasitic capacitance is formed at a position, which is a central portion of shield portion 12ba and overlaps with ~~a~~ the contact hole 18 to be described later. The capacitance portion 12bb of the second projecting portion 12b is formed in such a way as to have a width narrower than that of the shield portion 12ba in the X-direction and extend in the Y-direction up to substantially the center of the unit pixel area 11a from the shield portion 12ba. The capacitance portion 12bb forms auxiliary capacitance between the source line 14 opposing thereto, as described later. --

Please replace the paragraph beginning at page 14, line 11, with the following rewritten paragraph:

49
- Next, a shield film is formed on the color layer 105 and patterned so as to form the black matrix 16 in the above-described shape. Sequentially, as illustrated in FIG. 3G, a resin solution film is formed on the passivation layer 104 by spin coating, etc., and the resultant film is hardened so as to form the overcoat layer 106. The overcoat layer 106 is made of transparent resin material with high flattening effect, which flattens irregularities due to the color layer 105 and black matrix 16. Then, the opening ~~105a~~ 106a is formed on the overcoat layer 106 by isotropic etching, -etc. The opening ~~105a~~ 106a is formed in such a way to cover the sidewall of the opening 105a of color layer 105 and have a gentle taper surface. In this way, the contact hole 18 having openings ~~103a~~ 106a, 104a, 105a is formed. -